

92 13. (Amended) An illumination system including a two-dimensional phase type element manufactured in accordance with a method as recited in [any one of Claims 2-12] Claim 2 or 3. X

14 15. (Amended) A device manufacturing method[,]  
comprising the steps of:

93 exposing a wafer to a device pattern[, by use of]  
using a projection exposure apparatus as recited in Claim 14; B

and

developing the exposed wafer.

Remarks

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The claims are 1-15, with claims 1-3 being independent. Claims 2-4, 6-13 and 15 have been amended to better define the invention. In particular, claims 8-13 have been amended to remove improper multiple dependency. Claims 2-4, 6, 7 and 15 have been amended as to formal matters. Consideration of the claims is respectfully requested.

Applicant's undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All

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correspondence should continue to be directed to our below  
listed address.

Respectfully submitted,

  
Attorney for Applicant

Registration No. 42,667

FITZPATRICK, CELLA, HARPER & SCINTO  
30 Rockefeller Plaza  
New York, New York 10112-3801  
Facsimile: (212) 218-2200

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